

Erratum to: Effects of Pulsed Laser Deposition Conditions on the Microstructure of $\text{Ca}_3\text{Co}_4\text{O}_9$ Thin Films

TING SUN,¹ HUEY HOON HNG,^{1,2} QINGYU YAN,¹ and JAN MA¹

1.—School of Materials Science & Engineering, Nanyang Technological University, Singapore 639798, Singapore. 2.—e-mail: ashhhng@ntu.edu.sg

Erratum to: Journal of ELECTRONIC MATERIALS Vol. 39, No. 9, 2010, pp. 1611–1615 DOI: 10.1007/s11664-010-1261-x

In the above mentioned article, a reference for our previous work [1] was regrettably omitted. The authors sincerely apologize for this error.

The citations that should have been made are as follows:

1. Page 1612, Paragraph 1, Lines 1–2: "...formation of the Ca_xCoO_2 secondary phase in the thin films.¹ The growth mechanism of ..."
2. Page 1613, Fig. 3 caption, Lines 2–3: "... under 20 Pa oxygen pressure at a substrate temperature of 750°C.¹ The peak at 33.24° for the 5-Hz..."

3. Page 1613, Paragraph 2, Lines 4–5: "... [1100] of the sapphire substrate on the cross-sectional area.¹ Figure 4a and b shows ..."
4. Page 1614, Fig. 6 caption, last line: "... during thin-film growth.¹"

REFERENCE

1. T. Sun, J. Ma, Q.Y. Yan, Y.Z. Huang, J.L. Wang, and H.H. Hng, *J. Cryst. Growth* 311, 4123 (2009). doi:[10.1016/j.jcrysgro.2009.06.044](https://doi.org/10.1016/j.jcrysgro.2009.06.044).